FORM PTO 1449 (modified)			ATTY DOCKET NO. 1960.30 DIV. I	APPLICATION N	o. 773674	PT0				
U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE LIST OF REFERENCES CITED BY APPLICANT(S)			APPLICANT TIMOTHY M. RICHARDSONI							
LIST OF REFERENCES CITED BY APPLICANT(S) (Use several sheets if necessary) Date Submitted to PTO: February 2, 2001			FILING DATE February 2, 2001		GROUP 2877	35				
'EXAMINER INITIAL	OOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLAS S	FILING DATE IF APPROPRIATE				
.N.S-	4,055,376	10/77	Daberko	350	10					
N.h.	5,622,796	4/97	Canestrari, et al.	430	22					
v.R.	4,616,241	10/86	Biefeld, et al.	357	16					
N Se	4,947,223	8/90	Biefeld, et al.	357	30					
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NA.	5,608,519	3/97	Gourley, et al.	356	318					
FOREIGN PATENT DOCUMENTS										
	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLAS S	TRANSLATION YES/NO/ OR ABSTRACT				
NA	0,214,1601	5/90	Europe	G01B	7/34	Abstract				
W.D.	2,702,277	9/94	France	G01M	11/00					
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					,					
OTHER DOCUMENT(S) linchiding Author, Title, Date, Pertinent Pages, Etc.)										
EXAMINER - DATE CONSIDERED 27 DET 2054										

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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FORM PTO 1449 (modified)			ATTY DOCKET NO. 1960.30 DIV. I	APPLICATION NO.	773674	0				
U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE			APPLICANT TIMOTHY M. RICHARDSONI							
LIST OF REFERENCES CITED BY APPLICANT(S) (Use several sheets if necessary)						5==				
Date Submitted to PTO: February 2, 2001			February 2, 2001	GROUP 2877	165 B					
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Nul-		Electro-Optical Systems Design; OTF Quantitative Image Analysis; David Smith, Dec. 1979.								
w.h.		Cambridge University Press; Nanofabrication And Biosystems, H. Hoch, L.W. Jelinski, and H.G. Craighead.								
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w.h.		JENOPTIK, Laser Optik Systeme								
J. (D.		"Contrast Transfer In Confocal Microscopy" by R. Oldenbourg, et al.								
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EXAMINER -	عد	mes. Pl	DATE CONSIDERED 2	3020	2004					

*EXAMINER: Initial if reference considered, whather or not citation is in conformance with MPEP 509; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to epplicant.

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